METHODS OF FORMING DUAL-DAMASCENE INTERCONNECT STRUCTURES USING ADHESION LAYERS USING ADHESION LAYERS HAVING HIGH INTERNAL COMPRESSIVE STRESSES

Field of the Invention

The present invention relates to integrated circuit fabrication methods and, more particularly, to methods of fabricating integrated circuit devices having metal interconnect structures therein.

Background of the Invention

Conventional methods of forming integrated circuit devices may include steps to form single and/or dual damascene structures using copper (Cu) as an electrical interconnect material. As illustrated by FIG. 1, a conventional dual-damascene copper wiring interconnect structure may be formed by patterning a first copper wiring pattern **12** within a first dielectric layer **10**, which is disposed on a semiconductor substrate (not shown). This first dielectric layer **10** may be formed as a porous SiCOH layer having a relatively low dielectric constant, which supports low capacitive coupling between adjacent conductive layers and patterns (not shown). This first copper wiring pattern **12** may be covered by an electrically insulating capping layer **14**, which may be formed as a SiCN layer. An adhesion layer **16** is also formed on the capping layer **14**. This adhesion layer **16**, which may also be referred to as a graded layer, is typically formed of a material having a strong adhesion strength, a low susceptibility to arching and undercutting (during processing) and a strong resistance to moisture absorption. An inter-metal dielectric (IMD) layer **18** is formed on the adhesion layer **16**, as illustrated. This IMD layer **18** may also be formed of a material having a relatively low dielectric constant. This IMD layer **18** may then be patterned (once or multiple times) to define an opening therein that exposes an upper surface of the first copper wiring

pattern **12**. Conventional techniques may then be used to fill the opening with a second copper wiring pattern, which includes a copper plug/via **20a** and a patterned copper wiring layer **20b** thereon.

As will be understood by those skilled in the art, via yield degradation (VYD) within interconnect structures may increase in response to copper void formation within the copper plug/via **20a**. These voids, which may form during processing, may be a byproduct of undercutting **22** of the adhesion layer **16** at an interface between a sidewall of the adhesion layer **16** and the copper plug/via **20a**. According to additional theories, the occurrence of VYD may be related to an outgassing of moisture from the adhesion layer **16** during back-end processing steps.

Summary of the Invention

Embodiments of the present invention include methods of forming an electrically insulating adhesion layer having reduced susceptibility to undercutting and moisture absorption during semiconductor processing. This adhesion layer is formed to have an internal compressive stress of greater than about 100 MPa and, more preferably, greater than about 150 MPa to thereby have sufficient ability to block etch-induced undercutting and moisture absorption. In particular, methods of forming electrical interconnect structures on semiconductor substrates including forming a first wiring pattern on a semiconductor substrate and then forming an electrically insulating adhesion layer on the first wiring pattern. The electrically insulating adhesion layer is formed to have an internal compressive stress of greater than about 100 MPa to thereby reduce its susceptibility to etching-induced undercutting and/or moisture absorption. An opening is then formed in the adhesion layer and the first wiring pattern is exposed by the opening. This opening may be formed using a selective etching step that exposes sidewalls of the adhesion layer to a chemical etchant and/or cleaning solutions.

Additional embodiments of the present invention include methods of forming dual-damascene copper wiring patterns by forming a first copper

wiring pattern on a semiconductor substrate and then covering the first copper wiring pattern with an electrically insulating capping layer. An electrically insulating adhesion layer having an internal compressive stress of greater than about 100 MPa and, more preferably, greater than about 150 MPa, is formed on the capping layer. An inter-metal dielectric (IMD) layer is formed on the adhesion layer. This IMD layer is then selectively etched to define an opening therein. This opening extends through the IMD layer, the adhesion layer and the capping layer and exposes an upper surface of the first copper wiring pattern. The opening is the filled with a second copper wiring pattern.

Still further embodiments of the present invention include methods of forming a dual-damascene copper wiring pattern by forming a first copper wiring pattern on a semiconductor substrate and forming an electrically insulating capping layer (e.g., SiCN layer) on the first copper wiring pattern. An electrically insulating adhesion layer having an internal compressive stress of greater than about 150 MPa is formed on the capping layer and an inter-metal dielectric layer is formed on the adhesion layer. An opening is then formed that extends through the inter-metal dielectric layer, the adhesion layer and the capping layer and exposes the first copper wiring pattern. A second copper wiring pattern is then formed in the opening and electrically contacts the first copper wiring pattern. According to these embodiments, the step of forming an electrically insulating adhesion layer includes depositing a silicon dioxide adhesion layer on the capping layer using source gases containing octamethylcyclotetrasilane (OMCTS) and helium (He).

An additional embodiment of the invention includes methods of forming a dual-damascene copper wiring patterns by forming a first dielectric layer comprising SiCOH on a semiconductor substrate and forming a first copper wiring pattern on the first dielectric layer. An electrically insulating capping layer comprising SiCN is formed on the first copper wiring pattern and then a silicon dioxide adhesion layer is deposited on the capping layer. This deposition step is performed using a first source

gas containing octamethylcyclotetrasilane (OMCTS) at a volumetric flow rate in a range from about 500 sccm to about 700 sccm and a second gas containing helium at a volumetric flow rate in a range from about 1000 to about 3000 sccm. In some cases, an additional third source gas such as oxygen may be provided at a volumetric flow rate of about 160 sccm. A second dielectric layer is formed on the adhesion layer and then an opening is formed that extends through the second dielectric layer, the adhesion layer and the capping layer and exposes the first copper wiring pattern. This opening is filled with a second copper wiring pattern.

Brief Description of the Drawings

FIG. 1 is a cross-sectional illustration of a conventional dual-damascene copper interconnect structure.

FIGS. 2A-2C are cross-sectional views of intermediate structures that illustrate methods of forming interconnect structures according to embodiments of the present invention.

Detailed Description of Preferred Embodiments

The present invention will now be described more fully hereinafter with reference to the accompanying drawings, in which preferred embodiments of the invention are shown. This invention may, however, be embodied in different forms and should not be construed as limited to the embodiments set forth herein. Rather, these embodiments are provided so that this disclosure will be thorough and complete, and will fully convey the scope of the invention to those skilled in the art. In the drawings, the thickness of layers and regions are exaggerated for clarity. It will also be understood that when a layer is referred to as being Aon@ another layer or substrate, it can be directly on the other layer or substrate, or intervening layers may also be present. Like numbers refer to like elements throughout.

Embodiments of the present invention include methods of forming an electrical interconnect structure having an adhesion layer therein, which has a reduced susceptibility to undercutting and moisture absorption during semiconductor processing. This adhesion layer is formed to have an

internal compressive stress of greater than about 100 MPa and, more preferably, greater than about 150 MPa, to thereby have sufficient ability to block etch-induced or cleaning-induced undercutting and moisture absorption. In particular, FIGS. 2A-2C illustrate methods of forming a dual-damascene copper wiring pattern by forming a first dielectric layer **100** on a semiconductor substrate **110**. This first dielectric layer **100** may be a relatively low-k dielectric layer such as a SiCOH layer having a thickness in a range from about 1,000Δ to about 8,000Δ. A first copper wiring pattern **120** is formed on the first dielectric layer **100**, as illustrated by FIG. 2A. This first copper wiring pattern **120** may be formed by patterning the first dielectric layer **100** to define a recess therein and then depositing a layer of copper metallization (not shown) into the recess. This layer of copper metallization may then be planarized for a sufficient duration to expose an upper surface of the first dielectric layer **100** and define a shape of the first copper wiring pattern **120**.

Thereafter, as illustrated by FIG. 2B, an electrically insulating capping layer **140** and a silicon dioxide adhesion layer **160** are formed on the first dielectric layer **100** and the first copper wiring pattern **120**. In some embodiments of the invention, the capping layer may be a SiCN layer having a thickness in a range from about 100Δ to about 1,000Δ. This silicon dioxide adhesion layer **160** is formed by depositing silicon dioxide on the capping layer **140**, using a combination of at least a first source gas containing octamethylcyclotetrasilane (OMCTS) and a second source gas containing helium in a deposition chamber. This deposition step may be performed at a pressure of about 5 torr and a temperature of about 350^{o}C, using OMCTS as a source gas at a flow rate of about 500 sccm, O_2 as a source gas at a flow rate of about 500 sccm and He as a source gas at a flow rate of about 1000 sccm.

In particular, in order to achieve a level of internal compressive stress within the adhesion layer **160** that exceeds 100 MPa and, more preferably, exceeds 150 MPa, the first source gas containing

octamethylcyclotetrasilane (OMCTS) is provided at a volumetric flow rate in a range from about 500 sccm to about 700 sccm and the second gas containing helium is provided at a volumetric flow rate in a range from about 1000 to about 3000 sccm. A third source gas comprising oxygen (O_2) may also be provided in combination with the first and second source gases. This third source gas may be provided at a volumetric flow rate of about 160 sccm.

Referring now to FIG. 2C, a second dielectric layer **180** is formed on the adhesion layer **160**. This second dielectric layer **180**, which may be formed using one or more separate deposition steps, may be a relatively low-k dielectric layer such as a SiCOH layer having a thickness in a range from about 1,000Δ to about 10,000Δ. An opening **210** is provided in the second dielectric layer **180** using one or more photolithographically defined etching steps. As illustrated, this opening **210** extends through the second dielectric layer **180**, the adhesion layer **160** and the capping layer **140** and exposes an upper surface of the first copper wiring pattern **120**. This opening **210** may then be cleaned using a diluted hydrofluoric acid (DHF) solution, which is exposed to sidewalls of the adhesion layer **160** having relatively high internal compressive stress. The opening **210** is then filled with a second copper wiring pattern **200**, as illustrated. This second copper wiring pattern **200** may be formed from a combination of separately deposited (and patterned) copper layers using conventional damascene processing techniques.

Accordingly, embodiments of the present invention illustrated and described herein result in the fabrication of an electrical interconnect structure that includes a first metal wiring pattern on a semiconductor substrate and an electrically insulating adhesion layer having an internal compressive stress of greater than about 150 MPa, on the first metal wiring pattern. A second metal wiring pattern is also provided that extends through an opening in the electrically insulating adhesion layer and directly contacting the first metal wiring pattern. The interconnect structure further

includes a low-k dielectric layer (e.g., SiCOH layer) extending on the electrically insulating adhesion layer. This low-k dielectric layer has an opening therein that is aligned with the opening in the electrically insulating adhesion layer.

In the drawings and specification, there have been disclosed typical preferred embodiments of the invention and, although specific terms are employed, they are used in a generic and descriptive sense only and not for purposes of limitation, the scope of the invention being set forth in the following claims.

THAT WHICH IS CLAIMED IS:

1. A method of forming an electrically conductive interconnect structure, comprising the steps of:

forming a first electrically conductive structure on a semiconductor substrate;

forming an electrically insulating adhesion layer having an internal compressive stress of greater than about 150 MPa, on the first electrically conductive structure;

selectively etching the electrically insulating adhesion layer to define an opening therein that exposes the first electrically conductive structure; and

filling the opening with a second electrically conductive structure.

2. The method of Claim 1, wherein said step of forming an electrically insulating adhesion layer comprises depositing a silicon dioxide adhesion layer on the first electrically conductive structure using source gases containing octamethylcyclotetrasilane (OMCTS) and helium (He).

3. The method of Claim 1, wherein said step of forming an electrically insulating adhesion layer comprises depositing a silicon dioxide adhesion layer using source gases containing octamethylcyclotetrasilane (OMCTS), oxygen (O2) and an inert carrier gas.

4. The method of Claim 1, wherein said step of filling the opening is preceded by a step of exposing a sidewall of the electrically insulating adhesion layer to a diluted hydrofluoric acid solution.

5. The method of Claim 1, wherein said step of forming a first electrically conductive structure is preceded by the steps of forming a SiCOH dielectric layer having a recess therein, on the semiconductor substrate; and wherein said step of forming a first electrically conductive structure comprises forming a filling the recess with a copper layer and planarizing the copper layer to define a copper wiring pattern within the recess.

6. The method of Claim 5, wherein said step of forming an electrically insulating adhesion layer is preceded by a step of forming an electrically insulating capping layer comprising SiCN directly on an upper surface of the copper wiring pattern.

7. The method of Claim 6, wherein said step of forming an electrically insulating adhesion layer comprises forming an electrically insulating adhesion layer directly on an upper surface of the electrically insulating capping layer.

8. The method of Claim 2, wherein said step of forming a first electrically conductive structure is preceded by the steps of forming a SiCOH dielectric layer having a recess therein, on the semiconductor substrate; and wherein said step of forming a first electrically conductive structure comprises forming a filling the recess with a copper layer and planarizing the copper layer to define a copper wiring pattern within the recess.

9. The method of Claim 8, wherein said step of forming an electrically insulating adhesion layer is preceded by a step of forming an electrically insulating capping layer comprising SiCN directly on an upper surface of the copper wiring pattern.

10. The method of Claim 9, wherein said step of forming an electrically insulating adhesion layer comprises forming an electrically insulating adhesion layer directly on an upper surface of the electrically insulating capping layer.

11. A method of forming a dual-damascene copper wiring pattern, comprising the steps of:

forming a first copper wiring pattern on a semiconductor substrate;

forming an electrically insulating capping layer on the first copper wiring pattern;

forming an electrically insulating adhesion layer having an internal compressive stress of greater than about 100 MPa, on the electrically insulating capping layer, by depositing a silicon dioxide adhesion layer using source gases containing octamethylcyclotetrasilance (OMCTS) and helium (He);

forming an inter-metal dielectric layer on the electrically insulating adhesion layer;

forming an opening that extends through the inter-metal dielectric layer, the electrically insulating adhesion layer and the electrically insulating capping layer and exposes the first copper wiring pattern; and

forming a second copper wiring pattern in the opening.

12. The method of Claim 11, wherein the silicon dioxide adhesion layer has an internal compressive stress of greater than about 150 MPa.

13. The method of Claim 11, wherein said step of forming a second copper wiring pattern is preceded by a step of exposing the electrically insulating adhesion layer to a diluted hydrofluoric acid solution.

14. The method of Claim 11, wherein the electrically insulating capping layer comprises SiCN.

15. The method of Claim 11, wherein the inter-metal dielectric layer comprises SiCOH.

16. A method of forming a dual-damascene copper wiring pattern, comprising the steps of:

forming a first dielectric layer comprising SiCOH on a semiconductor substrate;

forming a first copper wiring pattern on the first dielectric layer;

forming an electrically insulating capping layer comprising SiCN on the first copper wiring pattern;

depositing a silicon dioxide adhesion layer on the electrically insulating capping layer, using a first source gas containing octamethylcyclotetrasilane (OMCTS) at a volumetric flow rate in a range from about 500 sccm to about 700 sccm and a second source gas containing helium at a volumetric flow rate in a range from about 1000 to about 3000 sccm;

forming a second dielectric layer comprising SiCOH on the silicon dioxide adhesion layer;

forming an opening that extends through the second dielectric layer, the silicon dioxide adhesion layer and the electrically insulating capping layer and exposes the first copper wiring pattern; and

forming a second copper wiring pattern in the opening.

17. The method of Claim 16, wherein said depositing step comprises depositing the silicon dioxide adhesion layer using a third source gas comprising oxygen (O_2) at a volumetric flow rate of about 160 sccm.

18. The method of Claim 16, wherein said depositing comprises depositing a silicon dioxide adhesion layer having an internal compressive stress of greater than about 150 MPa.

19. A method of forming an electrical interconnect structure, comprising the steps of:

forming a dielectric layer on a semiconductor substrate;

forming a metal wiring pattern on the dielectric layer; and

depositing an adhesion layer on the metal wiring pattern using a first source gas containing octamethylcyclotetrasilane (OMCTS) at a volumetric flow rate in a range from about 500 sccm to about 700 sccm and a second gas containing helium at a volumetric flow rate in a range from about 1000 to about 3000 sccm.